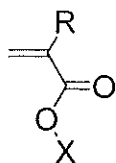


NOVEL ACRYL MONOMER, POLYMER AND RESIST COMPOSITION COMPRISING THE SAME

ABSTRACT

Provided are an acrylic monomer represented by the following formula (1),
 5 which is useful as a monomer for forming a resist additive that exhibits high
 hydrophobicity before development at the time of forming a resist pattern, thus
 separating water from the resist and preventing low molecular weight substances,
 hydrophilic additives and the like, which are constituent materials in the resist, from
 being eluted into water, and is converted to be hydrophilic after development so that
 10 pattern defects after development can be reduced; a polymer for resist additive
 containing a repeating unit derived from the acrylic monomer; and a resist composition
 comprising the polymer:

[Chemical Formula 1]

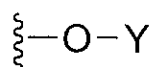


15 wherein in formula (1),

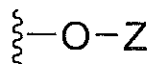
R represents a hydrogen atom or an alkyl group having 1 to 8 carbon atoms;

X represents a branched or cyclic hydrocarbon group having 3 to 30 carbon
 atoms and containing a functional group represented by the following formula (2) and at
 least one functional group represented by the following formula (3):

20 [Chemical Formula 2]



[Chemical Formula 3]



wherein in formulas (2) and (3),

25 Y represents a base-labile group containing a fluorine atom; and

Z represents a base-labile group containing no fluorine atom.

(no suitable figure)